## CLAIMS

What is claimed is:

1. a measuring system of a gas-stream environment, said measuring system comprises:

a stage, wherein said stage is located on a transport apparatus and used to place a wafer;

a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen and is used to exhaust said gas;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage and is used to exhaust said gas;

a first tube, wherein said first tube is connected with said first gas nozzle and said gas supplier;

a second tube, wherein said second tube is connected with said second gas nozzle and said gas supplier;

a transport slot, wherein said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce a attraction to remove said gas.

2. The system according to claim 1, wherein said first tube comprises a flow rate regulating valve.

3. The system according to claim 1, wherein said second tube comprises a flow rate regulating valve.

4. The system according to claim 1, wherein said gas-extracting apparatus comprises a gas-extracting motor.

5. The system according to claim 1, wherein said gas-extracting apparatus comprises a venturi structure.

6. The system according to claim 1, wherein said gas is a inert gas.

7. The system according to claim 1, wherein said gas is a nitrogen.

8. The system according to claim 1, wherein said gas supplier comprises a flow rate regulating valve.

9. a measuring system of a gas-stream environment, said measuring system comprises:

a stage, wherein said stage is located on a transport apparatus and used to place a wafer;

a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen to exhaust said gas and comprises a first flow rate regulating valve;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage to exhaust said gas and comprises a first flow rate regulating valve;

a first tube, wherein said first tube is connected with said first gas nozzle and said gas supplier;

a second tube, wherein said second tube is connected with said second gas nozzle and said gas supplier;

a transport slot, wherein said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce a attraction to remove said gas.

10. The system according to claim 9, wherein said first tube comprises a flow rate regulating valve.

11. The system according to claim 9, wherein said second tube comprises a flow rate regulating valve.

12. The system according to claim 9, wherein said gas-extracting apparatus comprises a gas-extracting motor.

13. The system according to claim 9, wherein said gas-extracting apparatus comprises a venturi structure.

14. The system according to claim 9, wherein said gas is a inert gas.

15. The system according to claim 9, wherein said gas is a nitrogen.

16. The system according to claim 9, wherein said gas supplier comprises a flow rate regulating valve.

17. a measuring system of a gas-stream environment, said measuring system comprises:

a stage, wherein said stage is located on a transport apparatus and used to place a wafer;

a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen and on said transport apparatus to exhaust said gas;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage and on said transport apparatus to exhaust said gas;

a first tube, wherein said first tube comprises a first flow rate regulating valve and is connected with said first gas nozzle and said gas supplier;

a second tube, wherein said second tube comprises a second flow rate regulating valve and is connected with said second gas nozzle and said gas supplier;

a transport slot, wherein said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce a attraction to remove said gas.

18. The system according to claim 17, wherein said gas-extracting apparatus comprises a venturi structure.

19. The system according to claim 17, wherein said gas is a inert gas.

20. The system according to claim 17, wherein said gas is a nitrogen.